



Amend
19/D 7/24/01
A. W. L. K.

Docket No.: M4065.0073/P073
(PATENT)

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:
Donald L. Yates

Application No.: 09/123,430

Group Art Unit: 2823

Filed: July 28, 1998

Examiner: B. Kebede

For: METHOD OF REDUCING SURFACE
CONTAMINATION IN
SEMICONDUCTOR WET-PROCESSING
VESSELS

AMENDMENT

Box Non-Fee Amendment
Commissioner for Patents
Washington, DC 20231

Dear Sir:

In response to the Office Action dated April 18, 2001 (Paper No. 18), please amend the above-identified U.S. Patent application as follows:

IN THE CLAIMS:

Please cancel claims 4, 16, 48-51, 53-57, 59 and 60.

Please add the following new claims:

--61. (new) A method for removing surface contaminants from an air/liquid interface of a semiconductor processing bath for processing semiconductor wafers, said method comprising:

07/15/2001 CCHAU1 00000092/09123430

01 FD:103

90.00 BP